

## **Semiconductor Capital Equipment - North America**

A North American manufacturer of capital equipment used in semiconductor wafer fabrication sought help on cleaning wafers during photoresist and etching. Sabol modeled the clean and etch baths (mixture of HF/NH<sub>3</sub>/HCl/H<sub>2</sub>O) and Sabol applied the classic simultaneous equilibrium analysis to the system of nine independent species, including use of activity coefficients. Sabol also provided insight on the temperature dependence, Pourbaix diagrams, and non-aqueous solvent systems for wafer cleaning and etching.

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Joseph E. Sabol, Ph.D.  
CHEMICAL CONSULTANT  
P.O.Box 085198  
Racine, WI 53408-5198 USA  
[www.chem-consult.com](http://www.chem-consult.com)

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